

PATENT ABSTRACTS OF JAPAN

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(11)Publication number : 64-082671
(43)Date of publication of application : 28.03.1989

(51)Int.Cl. H01L 29/78
H01L 21/318

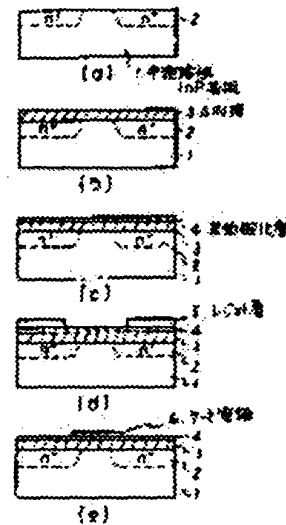
(21)Application number : 62-242134 (71)Applicant : NEC CORP
(22)Date of filing : 25.09.1987 (72)Inventor : TATSUMI ASAKO

(54) MANUFACTURE OF MIS FIELD-EFFECT TRANSISTOR

(57)Abstract:

PURPOSE: To improve reliability and to reduce irregularities in characteristics by forming an oxide layer as a protective film against a resist developer on an AlN film in a MIS FET having AlN as a gate insulating film on a III-V compound semiconductor substrate.

CONSTITUTION: An n+ type layer 2 is formed by atomic layer epitaxial growth as a source and drain electrode contact layer on a semi-insulating InP substrate 1. Then, an AlN film 3 is formed as a gate insulating film by an organic metal vapor growing method on the substrate 1. Thereafter, the surface of the film 3 is exposed with an oxygen atmosphere at 100° C., thereby forming a surface oxide film 4 having 50Å of thickness. Subsequently, a photoresist pattern 5 for forming a gate electrode 6 is formed of positive type resist. Then, aluminum is deposited by a resistance heating method on the whole surface of a sample. Thereafter, the pattern 5 is removed to be lifted OFF, and a gate electrode 6 is formed. Then, it can prevent electric characteristics of the AlN and a boundary between the AlN and a semiconductor from being deteriorated with a resist developer.



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[Date of request for examination]
[Date of sending the examiner's decision of rejection]
[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]
[Date of final disposal for application]
[Patent number]
[Date of registration]
[Number of appeal against examiner's decision of rejection]
[Date of requesting appeal against examiner's decision of rejection]
[Date of extinction of right]